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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Complete if Known	
		Application Number	09 / 898,521
		Filing Date	July 3, 2001
		First Named Inventor	Charles D. SCHAPER
		Group Art Unit	
		Examiner Name	
		Attorney Docket Number	STAN MXL 001

Sheet	1	of	1
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OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
SPH		Stephen CHOU, Peter KRAUSS, & Preston RENSTROM. "Imprint Lithography with 25-Nanometer Resolution", Science Vol. 272, April 5, 1996 pp. 85-87, USA.	
SPH		Stephen CHOU, Peter KRAUSS, & Preston RENSTROM. "Nanoimprint Lithography", Journal of Vacuum Science & Technology B Vol. 14(6), Nov/Dec. 1996 pp. 4129-4133, USA.	
SPH		Babak HEIDARI, Ivan MAXIMOV, Eva-Lena SARWE, & Lars MONTELIUS, "Large scale nanolithography using nanoimprint lithography", Journal of Vacuum Science & Technology B Vol. 17(6), Nov/Dec. 1999 pp. 2962-2964, USA.	
SPH		Jan HAISMA, Martin VERHEIJEN, Kees VAN DEN HEUVEL, & Jan VAN DEN BERG, "Mold-assisted nanolithography: A process for reliable pattern replication", Journal of Vacuum Science & Technology B Vol. 14(6), Nov/Dec. 1996 pp. 4124-4128, USA.	
SPH		Thomas WHIDDEN, David FERRY, Michael KOZICKI, Enoch KIM, Amit KUMAR, James WILBUR, & George WHITESIDES, "Pattern transfer to silicon by microcontact and RIE", in Nanotechnology Vol. 7, 1996, pp. 447-451, UK.	
SPH		James WILBUR, Amit KUMAR, Hans BIEBUYCK, Enoch KIM, & George WHITESIDES, "Microcontact printing of self-assembled monolayers: applications in microfabrication", in Nanotechnology Vol. 7, 1996, pp. 452-457, UK.	
SPH		Younan XIA & George WHITESIDES, "Soft lithography", in Annual Reviews of Material Science Vol. 28, 1998, pp. 153-184, USA.	
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SPH		P. RUCHHOEFT, M. COLBURN, B. CHOI, H. NOUNU, S. JOHNSON, T. BAILEY, S. DAMLE, M. STEWART, J. EKERDT, S.V. SREENIVASAN, J.C. WOLFE, & C. Grant WILLSON, "Patterning curved surfaces: Template generation by ion beam proximity lithography and relief transfer by step and flash imprint lithography", Journal of Vacuum Science & Technology B Vol. 17(6), Nov/Dec. 1996 pp. 2965-2969, USA.	

Examiner Signature	Mohamedulla	Date Considered	8/9/04
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